

**AMENDMENT TRANSMITTAL LETTER (Large Entity)**  
 Applicant(s): Apostolos Voutsas

 Docket No.  
 SLA0592

 Serial No  
 09/893,866

 Filing Date  
 June 28, 2001

 Examiner  
 Asok K. Sarkar

 Group Art Unit  
 2829

Invention: Method for Forming Silicon Films with Trace Impurities

**FAX COPY RECEIVED****TO THE COMMISSIONER FOR PATENTS:****SEP 19 2002**

Transmitted herewith is an amendment in the above identified application.

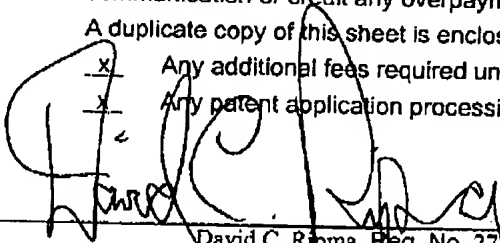
The fee has been calculated and is transmitted as shown below.

TECHNOLOGY CENTER 2800

**CLAIMS AS AMENDED**

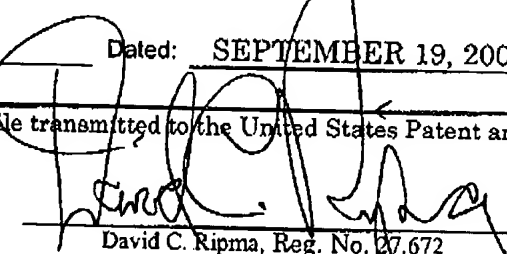
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST # PREV. PAID FOR	NUMBER OF EXTRA CLAIMS PRESENT	RATE	ADDITIONAL FEE
TOTAL CLAIMS	25 -	23 =	2	x \$18.00	\$36.00
INDEP. CLAIMS	3 -	3 =	0	x \$84.00	\$0.00
Multiple Dependent Claims (check if applicable) _____					\$0.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$36.00

- ☐ No additional fee is required for amendment.  
☒ Please charge Deposit Account No. 19-1457 in the amount of \$36.00.  
 A duplicate copy of this sheet is enclosed.  
 A check in the amount of \_\_\_\_\_ to cover the filing fee is enclosed.  
☒ The Commissioner is hereby authorized to charge payment of the following fees associated with this communication or credit any overpayment to Deposit Account No. 19-1457.  
 A duplicate copy of this sheet is enclosed.  
☒ Any additional fees required under 37 C.F.R. 1.16.  
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 David C. Ripma, Reg. No. 27,672

 Dated: **SEPTEMBER 19, 2002**

I hereby certify that this correspondence is being facsimile transmitted to the United States Patent and Trademark Office under 37 C.F.R. §1.8 at Fax No. (703) 872-9318 on July 30, 2002.

  
 David C. Ripma, Reg. No. 27,672

Note: Each paper must have its own certificate or transmission, or this certificate must identify each submitted paper. The papers submitted include:

- |  |            |
|--|------------|
| <input checked="" type="checkbox"/> This Amendment Transmittal Letter (Duplicate Attached)           | 2 page(s)  |
| <input checked="" type="checkbox"/> Response under 37 CFR § 1.111                                    | 23 page(s) |
| <input checked="" type="checkbox"/> Attachments  | 0 page(s)  |
| <input type="checkbox"/> Petition for Extension of Time under 37 C.F.R. § 1.136 (Duplicate Attached) | page       |

Total pages, including this Transmittal: 25

#7/B  
9-24-2  
Robert  
A Final

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Inventors: Apostolos Voutsas

Serial No.: 09/893,866

Filed: June 28, 2001

Title: METHOD FOR FORMING  
SILICON FILMS WITH TRACE  
IMPURITIES

ATTORNEY FILE NO.  
SLA592

Do not  
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**CERTIFICATION UNDER 37 CFR § 1.8**

I hereby certify that the documents referred to as enclosed herein are being deposited with the United States Postal Service as first class mail on this date 9/19/02 in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.

Date

Signature

David E. Ripma  
Reg. No. 27,872

**BOX RESPONSES**

Assistant Commissioner for Patents  
Washington, D.C. 20231

09/25/2002 JROBERTS

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**AMENDMENT AND REQUEST FOR RECONSIDERATION**

In response to a Final Office Action filed July 31, 2002, please accept the following amendments and reconsider.

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SEP 19 2002

**IN THE CLAIMS:**

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Please amend claims 6, 9, 19, and 22 as follows.

1. (Unchanged) In the fabrication of liquid crystal displays (LCDs), a method for forming silicon films with a controlled amount of trace impurities, the method comprising:

forming a target including silicon and a first concentration of a first impurity;

supplying a substrate; and